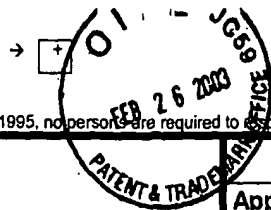




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PTO/SB/08A (08-00)

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U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

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Substitute for form 1449B/PTO				<b>Complete if Known</b>	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)				Application Number	09/698,317
				Filing Date	October 27, 2000
				First Named Inventor	Choi et al.
				Group Art Unit	2859
				Examiner Name	Unassigned T. Dougherty
Sheet	2	of	2	Attorney Docket Number	PA09-06V02

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cita No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>	
TMD	B10	LIN, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, New York 10598.		
TMD	B11	COWIE, "Polymers: Chemistry and Physics of Modern Materials", 1991, pp. 408-409, 2 <sup>nd</sup> Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 <sup>th</sup> Street, NY, NY 10001-2291.		
TMD	B12	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers", Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).		
TMD	B13	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution", Science, Apr. 5, 1996, pp. 85-87, vol. 272.		
TMD	B14	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput", Microelectronic Engineering, 1997, pp. 237-240, vol. 35.		
TMD	B15	XIA et al., "Soft Lithography", Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.		

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Examiner Signature	Thomas M. Dougherty	Date Considered	2-12-04
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 2

<b>Application Number</b>	09/698,317
<b>Filing Date</b>	October 27, 2000
<b>First Named Inventor</b>	Choi et al.
<b>Group Art Unit</b>	2834
<b>Examiner Name</b>	Dougherty, Thomas M.
<b>Attorney Docket Number</b>	UTS-09-06V02

## U.S. PATENT DOCUMENTS

[illegible]

<sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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Thomas M. Dougherty February 12, 2004

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# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet

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of

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**Application Number**

09/698,317

## Filing Dat

**October 27, 2000**

**First Name of Inventor**

Choi et al.

## Group Art Unit

2834

**Examiner Name**

**Dougherty, Thomas M.**

Attorney Docket Number

UTS-09-06V02

Examiner  
Initials\*Cite  
No. $\tau^2$ 

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**C3**

Feldman et al., "Wafer Chuck for Magnification correction in X-ray Lithography," *Journal of Vacuum Science and Technology*, Nov/Dec 1998, pp. 3476-3479, vol. B 16(6).

**Examiner  
Signature**

Thomas M. Kephart

Date  
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Feb. 12, 2004

<sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

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**Form PTO-1449** (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
tmj	A1	3,807,027	4/1974	Heisler	29	423	
tmj	A2	3,807,029	4/1974	Troeger	29	436	
tmj	A3	3,811,665	5/1974	Seelig	26		
tmj	A4	4,062,600	12/1977	Wyse	384	225	
tmj	A5	4,098,001	7/1978	Watson	33	644	
tmj	A6	4,155,169	5/1979	Drake et al.	33	644	
tmj	A7	4,202,107	5/1980	Watson	33	644	
tmj	A8	4,267,212	5/1981	Sakawaki	427	240	
tmj	A9	4,337,579	7/1982	De Fazio	33	644	
tmj	A10	4,355,469	10/1982	Nevins et al.	267	150	
tmj	A11	4,414,750	11/1983	De Fazio	267	166	
tmj	A12	4,451,507	5/1984	Beltz et al.	427	240	
tmj	A13	4,610,442	9/1986	Oku et al.	269	73	
tmj	A14	4,694,703	11/1987	Routson	79	5F	
tmj	A15	4,731,155	3/1988	Napoli et al.	216	44	
tmj	A16	4,763,886	8/1988	Takei	269	73	
tmj	A17	4,929,083	5/1990	Brunner	356	400	
tmj	A18	4,959,252	11/1990	Bonnebat et al.	428	64.7	
tmj	A19	5,072,126	12/1991	Progler	250	548	
tmj	A20	5,110,514	5/1992	Soane	264	496	
tmj	A21	5,126,006	6/1992	Cronin et al.	438	702	
tmj	A22	5,204,739	4/1993	Domenicali	348	79	
tmj	A23	5,240,550	8/1993	Boehnke et al.	216	24	
tmj	A24	5,348,616	9/1994	Hartman et al.	216	48	
tmj	A25	5,392,123	2/1995	Marcus et al.	356	625	
tmj	A26	5,425,964	6/1995	Southwell et al.	427	10	
tmj	A27	5,452,090	9/1995	Progler et al.	356	401	

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**Form PTO-1449** (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

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APPLICANT: Choi et al.

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**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
DMB	A28	5,480,047	1/1996	Tanigawa et al.	216	12	
DMB	A29	5,512,131	4/1996	Kumar et al.	438	355	
DMB	A30	5,515,167	5/1996	Ledger et al.	356	595	
DMB	A31	5,545,367	10/1996	Bae et al.	264	401	
DMB	A32	5,566,584	10/1996	Briganti et al.	74	490.01	
DMB	A33	5,633,505	5/1997	Chung et al.	250	491.1	
DMB	A34	5,724,145	3/1998	Kondo et al.	356	632	
DMB	A35	5,753,014	5/1998	Van Rijn	96	12	
DMB	A36	5,760,500	6/1998	Kondo et al.	310	12	
DMB	A37	5,772,905	6/1998	Chou	216	44	
DMB	A38	5,776,748	7/1998	Singhvi et al.	435	180	
DMB	A39	5,779,799	7/1998	Davis	118	663	
DMB	A40	5,802,914	9/1998	Fassler et al.	74	110	
DMB	A41	5,877,036	3/1999	Kawai	438	16	
DMB	A42	5,877,861	3/1999	Ausschnitt et al.	356	401	
DMB	A43	5,888,650	3/1999	Calhoun et al.	428	354	
DMB	A44	5,900,160	5/1999	Whitesides et al.	216	41	
DMB	A45	5,912,049	6/1999	Shirley	427	240	
DMB	A46	5,942,871	8/1999	Lee	318	611	
DMB	A47	5,948,470	9/1999	Harrison et al.	427	148	
DMB	A48	5,952,127	9/1999	Yamanaka	430	5	
DMB	A49	6,038,280	3/2000	Rossiger et al.	378	50	
DMB	A50	6,039,897	3/2000	Lochhead et al.	264	1,24	
DMB	A51	6,046,056	4/2000	Parce et al.	204	403.05	
DMB	A52	6,051,345	4/2000	Huang	430	5	
DMB	A53	6,074,827	6/2000	Nelson et al.	435	6	
DMB	A54	6,091,485	7/2000	Li et al.	356	73	
	A55	6,128,085	10/2000	Buermann et al.	356	369	

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*Shennan M. Ruppberg*

DATE CONSIDERED:

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**Form PTO-1449** (modified)

List of Patents and Publications

For Applicant's Information

Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

GROUP: 2859

FILING DATE: October 27, 2000

**U.S. PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
JMD	A56	6,143,412	11/2000	Schueller et al.	428	408	
JMD	A57	6,168,845	1/2001	Fontana, Jr. et al.	428	65.5	
JMD	A58	6,180,239	1/2001	Whitesides et al.	428	411.1	
JMD	A59	6,204,922	3/2001	Chalmers	356		
JMD	A60	6,334,960	1/2002	Wilson et al.	216	52	

**FOREIGN PATENT DOCUMENTS**

EXAM. INITIALS	REF. DES.	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO
JMD	A61	00/54107	9/2000	WO	608F	7/00	
JMD	A62	01/33232	5/2001	WO	601R	—	
JMD	A63	01/33300	5/2001	WO	402K	5/24	
JMD	A64	244884	3/1987	EP	829C	33/34	
JMD	A65	733455	9/1996	EP	829C	33/34	NO
JMD	A66	2800476	7/1978	DE	603C	5/08	NO
JMD	A67	19648844	11/1999	DE	829C	59/02	NO
JMD	A68	1-196749	8/1989	JP	611B	7/26	NO

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*Thomas M. Dougherty*

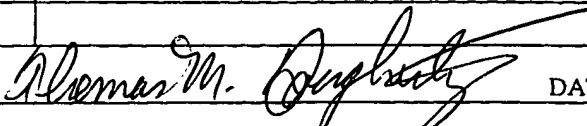
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<b>Form PTO-1449</b> (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	RECEIVED GROUP 3600 JUN 26 2002 09/698,317
<b>OTHER REFERENCES</b> (Including Author, Title, Date, Pertinent Pages, Etc.)			
tmb	A69	Stewart, D.; "A Platform with Six Degrees of Freedom", Proc. of Inst. Mech. Engrs., 1965, 180, 371-378.	
tmb	A70	Paros, J.M.; Weisbord, L.; "How to Design Flexure Hinges", Machine Design, 1965, 151-156.	
tmb	A71	Raibert, M.H.; Craig, J.J.; "Hybrid Position/Force Control of Manipulators", 1981, 102, 126-133.	
tmb	A72	Hogan, Neville; "Impedance Control: An Approach to Manipulation", Journal of Dynamic Systems, Measurement and Control, 1985, 107, 1-7.	
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tmb	A74	Tomita, Y. et al.; "6-Axes Motion Control Method for Parallel-Linkage-Type Fine Motion Stage", Journal of Japan Society of Precision Engineering, 1992, 118-124.	
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tmb	A77	Arai, T.; Larssonneur, R.; Jaya, Y.M.; "Calibration and Basic Motion of a Micro Hand Module", Proc. of IECON, 1993, 1660-1665.	
tmb	A78	Peng, Zhi-Xin; Adachi, N.; "Compliant Motion Control of Kinematically Redundant Manipulators", IEEE Transactions on Robotics and Automation, 1993, 9, 831-837.	
tmb	A79	Rong, Y.; Zhu, Y.; Luo, Z.; Liu, X.; "Design and Analysis of Flexure-Hinge Mechanism Used in Micro-Positioning Stages", ASME, 1994, 2, 979-985.	
tmb	A80	Hashimoto, M.; Imamura, Y.; "Design and Characteristics of a Parallel Link Compliant Wrist", IEEE International Conference on Robotics and Automation, 1994, 2457-2462.	
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tmb	A82	Ananthasuresh, S.; Kikuchi, N.; "Strategies for Systematic Synthesis of Compliant MEMS", ASME, 1994, 2, 677-686.	
tmb	A83	Arai, T.; Tanikawa, T.; Merlet, J.P.; Sendai, T.; "Development of a New Parallel Manipulator with Fixed Linear Actuator", Proc. of Japan/USA Symposium on Flexible Automation, 1996, 1, 145-149.	
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tmb	A86	Pernette, Eric; Henein, Simon; Magnani, Ivo; Clavel, Reymond; "Design of Parallel Robots in Microrobotics", Robotica, 1997, 15, 417-420.	

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<b>Form PTO-1449</b> (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		ATTY. DKT. NO. 5119-08601 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859
tmj	A87	Rong, L.; Guanghui; "Dynamics of Parallel Mechanism with Direct Compliance Control", IEEE, 1997, 1753-1758.	
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tmj	A94	Koseki, Y. et al.; "Design and Accuracy Evaluation of High-Speed and High Precision Parallel Mechanism", Proc. of IEEE, Intl. Conf. on Robotics & Automation, 1998, 1340-1345.	
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tmj	A96	Mansky, P. et al.; "Large-Area Domain Alignment in Block Copolymer Thin Films Using Electric Fields", Macromolecules, 1998, 31, 4399-4401.	
tmj	A97	Wang, W.; Loh, R.; Gu, E.; "Passive Compliance Versus Active Compliance in Robot-Based Automated Assembly Systems", Industrial Robot, 1998, 25, 48-57.	
tmj	A98	Scheer, H.C. et al.; "Problems of Nanoimprinting Technique for Nanometer Scale Pattern Definition", Journal of Vacuum Science and Technology, 1998, 16, 3917-3921.	
tmj	A99	Xia, Y.; Whitesides, George; "Soft Lithography", Annu. Rev. Mater. Sci., 1998, 28, 153-184.	
tmj	A100	Tajbakhsh, H. et al.; "Three-Degree-of-Freedom Optic Mount for Extreme Ultraviolet Lithography", ASPE, 1998, 18, 359-362.	
tmj	A101	Lee, Dong Sung et al.; "Ultra Precision Positioning System for Servo Motor-Piezo Actuator Using Dual Servo Loop and Digital Filter Implementation", ASPE, 1998, 18, 287-290.	
tmj	A102	Wu, Wei et al.; "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography", 1998, Journal of Vacuum Science and Technology, 1998, 16, 3825-3829.	
tmj	A103	Ohya, Y. et al.; "Development of 3-DOF Finger Module for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 894-899.	
tmj	A104	Tanikawa, T. et al.; "Development of Small-Sized 3 DOF Finger Module in Micro Hand for Micro Manipulation", Proc. of IEEE, Intl. Conf. on Intelligent Robots and Systems, 1999, 876-881.	
tmj	A105	Colburn, M. et al.; "Step and Flash Imprint Lithography: New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, 3676, 379-389.	

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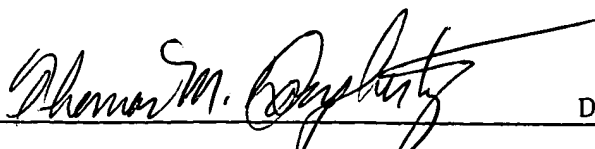
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Information Disclosure Statement--PTO 1449 (modified)

<b>Form PTO-1449</b> (modified) List of Patents and Publications For Applicant's Information Disclosure Statement (Use several sheets if necessary)		PATTY. DKT. NO. 5119-0860 APPLICANT: Choi et al. FILING DATE: October 27, 2000	SERIAL NO. 09/698,317 GROUP: 2859 JUN 26 2002 <b>GROUP 3600</b>
DMB	A106	Lucas Aerospace, Free-Flex Pivot Catalog, 1999	
DMB	A107	Goldfarb, M.; Speich, J.E.; "A Well-Behaved Revolute Flexure Joint for Compliant Mechanism Design", Journal of Mech. Design, 1999, 121, 424-429.	
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DMB	A109	Hexel Corporation, Tornado 2000 System Specifications, 1999, from <a href="http://www.hexel.com">www.hexel.com</a>	
DMB	A110	Physik Instruments, PI Online-Catalog, 1999, from <a href="http://www.physikinstrument.com">www.physikinstrument.com</a>	
DMB	A111	Chou, Stephen; Zhuang, Lei; "Lithographically-induced Self Assembly of Periodic Micropillar Arrays", Journal of Vacuum Science and Technology, 1999, 17, 3197-3202.	
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DMB	A113	Vanderbilt University Office of Transfer Technology; VU 9730 Specifications for Improved Flexure Device; 2001, from <a href="http://www.vanderbilt.edu">www.vanderbilt.edu</a>	
DMB	A114	Stix, Gary; "Getting More from Moore's", Scientific American, 2001, from <a href="http://www.scientificamerican.com">www.scientificamerican.com</a>	
DMB	A115	Trilogy Systems, Linear Motors 310 Specification, 2001, from <a href="http://www.trilogysystems.com">www.trilogysystems.com</a>	
DMB	A116	Choi, B.J. et al.; "Design of Orientation Stages for Step and Flash Imprint Lithography", Precision Engineering, 2001, 25, 192-199.	
DMB	A117	PCT International Search Report for PCT/US 00/30041, dated 10/15/2001	
DMB	A118	PCT International Search Report for PCT/US 01/26049, dated 2/19/2002	

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